

L Number	Hits	Search Text	DB	Time stamp
1	1	("5670210").PN.	USPAT	2003/12/17 09:59
3	2	((118/52,56,58,62,63).CCLS.) and catalyst and (drying adj gas)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/17 10:33
4	20	((118/52,56,58,62,63).CCLS.) and catalyst and (nitrogen or (water adj vapor))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/17 10:33
5	70	((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) with (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/17 10:36
6	158	((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) same (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer)	USOCR USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/17 10:36
7	60	((118/52,56,58,62,63).CCLS.) and ((mesh or screen or filter) with (gas or vapor)) and (substrate or wafer)	USOCR USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/17 10:38
8	8	((((118/52,56,58,62,63).CCLS.) and catalyst and (drying adj gas)) ((118/52,56,58,62,63).CCLS.) and catalyst and (nitrogen or (water adj vapor))) (((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) with (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer)) (((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) same (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer)) ((118/52,56,58,62,63).CCLS.) and ((mesh or screen or filter) with (gas or vapor)) and (substrate or wafer))) and @pd>=20030814	USOCR USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/17 10:39
2	2	((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer) and @pd>=20030814	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/17 10:46
-	4302	(118/52,56,58,62,63).CCLS.	USOCR USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/14 13:28
-	17	((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer)	USOCR USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/14 14:08

-	17	((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 11:45
-	247	((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/04 15:39
-	48	((118/52,56,58,62,63).CCLS.) and ((mesh or screen or filter) with (gas or vapor)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/12/17 10:37
-	46	(((118/52,56,58,62,63).CCLS.) and ((mesh or screen or filter) with (gas or vapor)) and (substrate or wafer)) not (((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 11:48
-	7	((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and ((substrate or wafer) same chuck) and (inlet same source)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 12:00
-	2	(((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and ((substrate or wafer) same chuck) and (inlet same source)) not (((118/52,56,58,62,63).CCLS.) and ((mesh or screen or filter) with (gas or vapor)) and (substrate or wafer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 12:01
-	2	("6287987").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 12:02
-	18	((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/04 15:40
-	260	((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 15:15
-	270	(((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer)) or (((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and (substrate or wafer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/04 15:41

-	14	(((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer)) or (((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and (substrate or wafer))) and @pd>=20020930	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/04 18:36
-	32201	((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) same (mesh or screen or filter) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 15:25
-	16606	((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) same (mesh or screen) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 16:22
-	7584	(((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) with (mesh or screen)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 16:28
-	64	(((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) with (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/12/17 10:35
-	146	(((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) same (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/12/17 10:36
-	82	(((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) same (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer)) not (((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) with (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 16:51
-	4433	(118/52,56,58,62,63).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/08/14 13:28
-	0	((118/52,56,58,62,63).CCLS.) and catalyst and (capillary adj pressure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/14 13:30
-	2	((118/52,56,58,62,63).CCLS.) and catalyst and (drying adj gas)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/17 10:33
-	17	((118/52,56,58,62,63).CCLS.) and catalyst and (nitrogen or (water adj vapor))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/17 10:33

-	1	((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer) and @pd>=20030308	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/12/17 10:31
-	61	((118/52,56,58,62,63).CCLS.) and (substrate or wafer) and @pd>=20030308	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/08/14 14:20